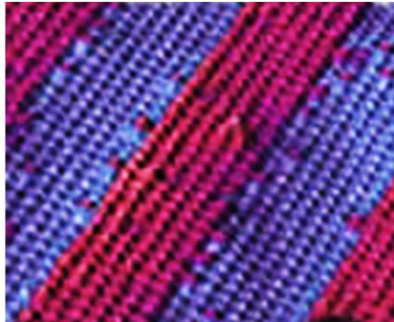




Growth

Nicolas Grandjean

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Growth III: fundamentals

nicolas.grandjean@epfl.ch 1

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Growth III: fundamentals

Quantum dots: Stranski-Krastanov growth mode, deterministic nucleation

Growth techniques: MOVPE, HVPE, MBE

2

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Growth III: fundamentals

Quantum dots: Stranski-Krastanov growth mode, deterministic nucleation

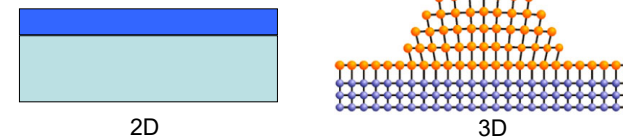
Growth techniques: MOVPE, HVPE, MBE

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Strain relaxation by elastic deformation of 3D islands

Stranski-Krastanov growth mode



Elastic energy release by relaxation at free-edges

But larger surface free energy

3D island formation: balance between elastic and surface energies

GaN/AlN $\Rightarrow$ 2.5 %

InAs/GaAs $\Rightarrow$ 7.2 %

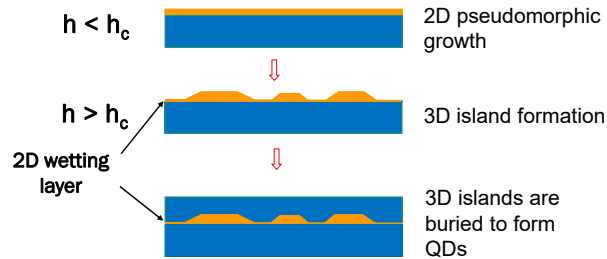
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Quantum dots

EPFL

Strain relaxation by elastic deformation of 3D islands



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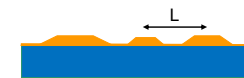
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Quantum dots

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What is needed for 3D island formation?

- Strain $\Rightarrow$ lattice mismatch must be high enough
- Low surface free energy
- Large surface diffusion length



crude criterion: $\lambda > L$

λ the surface diffusion length and L mean distance between islands

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Quantum dots

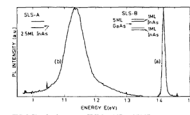
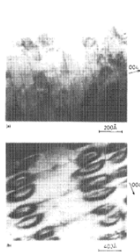
EPFL

First report of semiconductor quantum dots

Growth by molecular beam epitaxy and characterization of InAs/GaAs strained-layer superlattices

L. Goldstein, F. Glas, J. Y. Marzin, M. N. Charasse, and G. Le Roux
Centre National d'Etudes des Télécommunications, 196 rue de Paris, 92220 France

(Received 26 July 1985; accepted for publication 4 September 1985)



In conclusion, binary InAs/GaAs SLS's have been grown on GaAs substrates. The sharp transition from the 2D nucleation to the 3D was observed by x-ray diffraction, STEM, and photoluminescence. It has been shown that even when In-rich clusters are formed, good crystalline quality material can be obtained. Also, specific and intense photoluminescence is associated with the cluster formation. These kinds of structures are thus proved to be of interest to study low-dimensional (< 2) objects showing good optical properties.

Appl. Phys. Lett. **47**, 1099 (1985)

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Quantum dots

EPFL

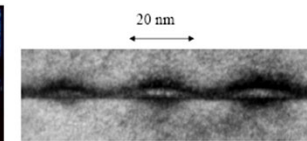
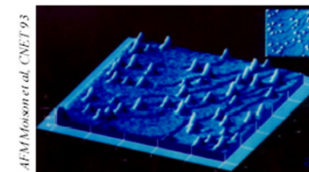
First report of SK-QDs (InAs/GaAs)

Self-organized growth of regular nanometer-scale InAs dots on GaAs

J. M. Moison, F. Houzay, F. Barthe, and L. Loprince
France Telecom, Centre National d'Etudes des Télécommunications Paris B, Laboratoire de Bagneux,¹⁾
196 Avenue Henri Ravera B.P. 107 F-92223 Bagneux Cedex, France

E. André and O. Vatel
France Telecom, Centre National d'Etudes des Télécommunications, Centre Norbert Segard, Chemin du Vieux Chêne BP 98 F-38243 Meylan Cedex, France

3D growth mode of highly strained InAs on GaAs + overgrowth by GaAs

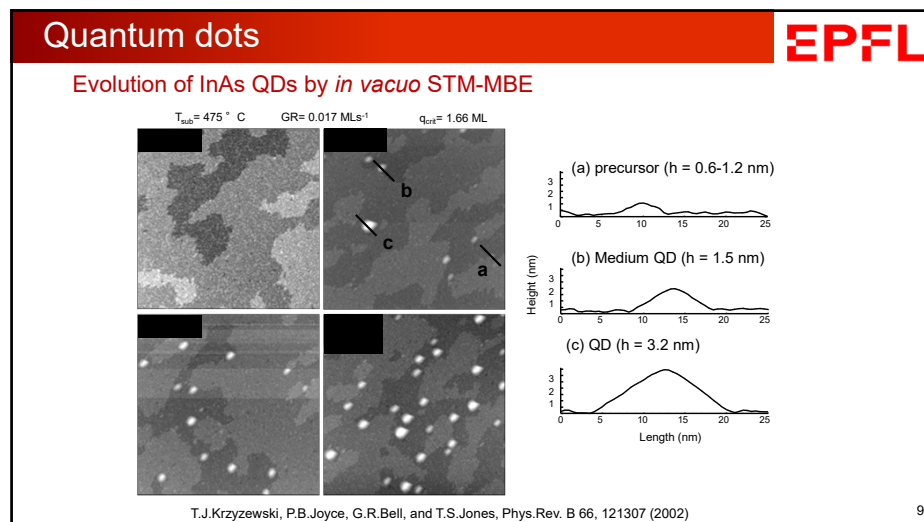


TEM A. Ponchet CNRS (95)

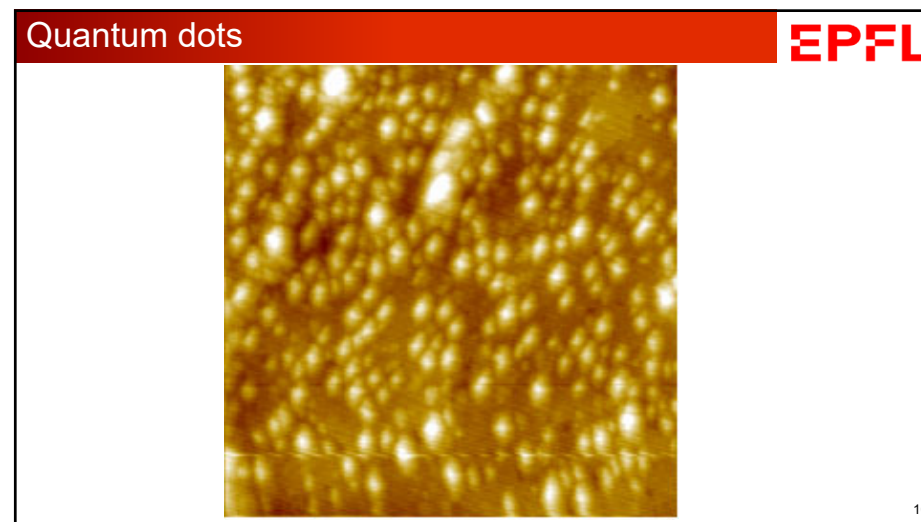
Appl. Phys. Lett. **64**, 196 (1994)

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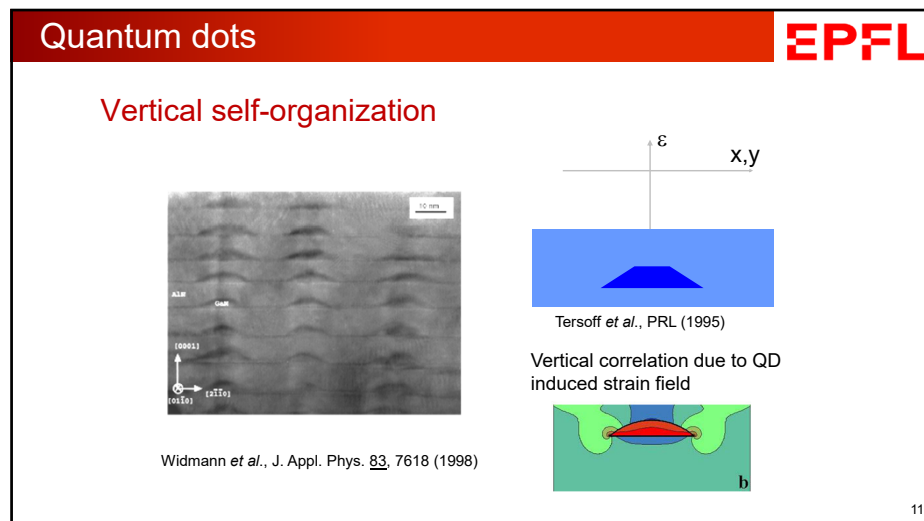
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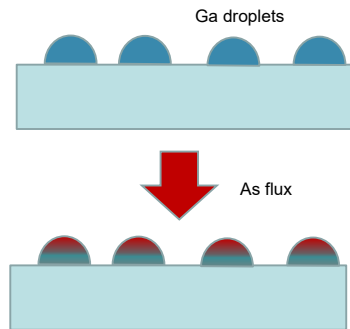
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Quantum dots

EPFL

Quantum dots without strain: GaAs/AlGaAs

Droplet epitaxy



C. Somaschini, S. Bietti, N. Koguchi, and S. Sanguinetti
Appl. Phys. Lett. 97, 203109 (2010)

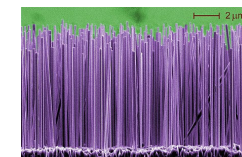
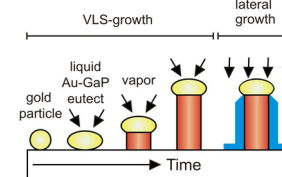
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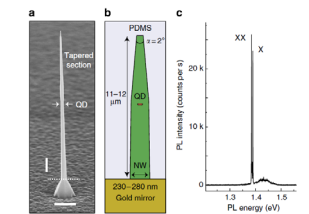
Quantum dots

EPFL

Quantum dots without strain: nanowires



Catalyst-free nanowires (GaN)



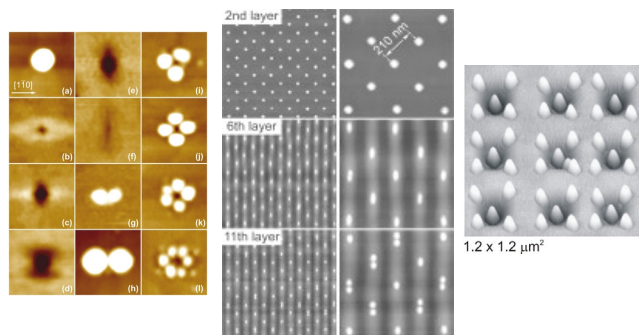
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Quantum dots

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Deterministic nucleation



R. Songmuang, S. Kiravittaya, and O. G. Schmidt
Applied Physics Letters 82, 2892 (2003)

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Growth - Basics

EPFL

Growth III: fundamentals

Quantum dots: Stranski-Krastanov growth mode, deterministic nucleation

Growth techniques: MOVPE, HVPE, MBE

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Growth techniques

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Main growth techniques:

Chemical

Hydride vapor phase epitaxy (HVPE)

Metal-organics vapor phase epitaxy (MOVPE)

Metal-organics chemical vapor deposition (MOCVD)

Physical

Molecular beam epitaxy (MBE)

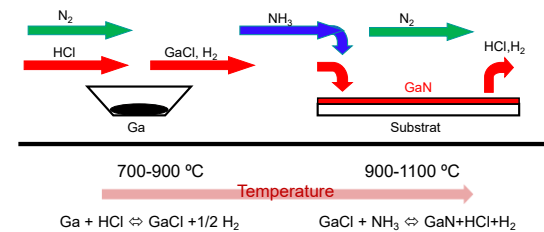
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Growth techniques

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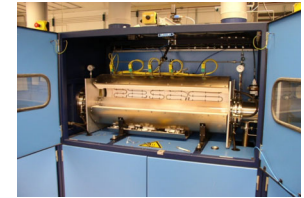
Hydride vapor phase epitaxy (HVPE)



Operates near equilibrium:

Growth rate > 100µm/h

Use for making free-standing GaN substrates



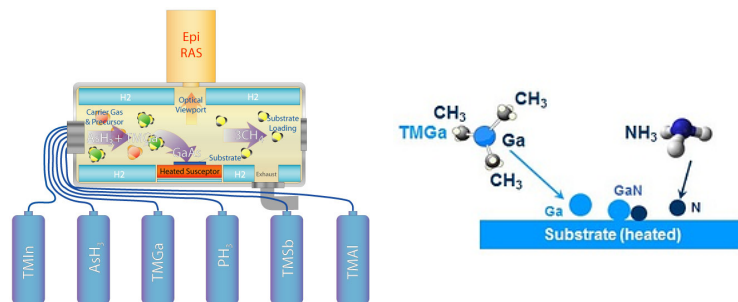
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Growth techniques

EPFL

Metal-organic vapor phase epitaxy (MOVPE)



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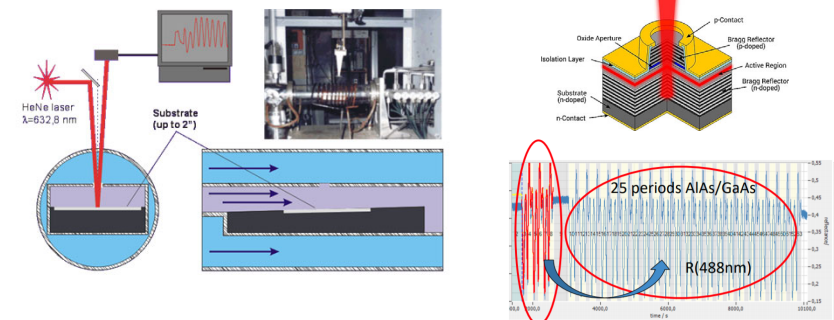
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Growth techniques

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Metal-organic vapor phase epitaxy (MOVPE)

In situ reflectivity



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Growth techniques

EPFL

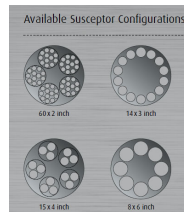
Metal-organic vapor phase epitaxy (MOVPE)

Production systems



GaAs/InP based Optoelectronics and Electronic Devices

Production systems



wafers per run: 124x4" and 48x6"



GaN blue LEDs (solid state lighting)

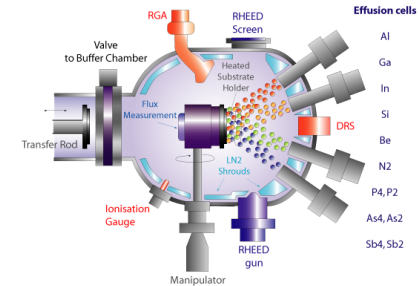
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Growth techniques

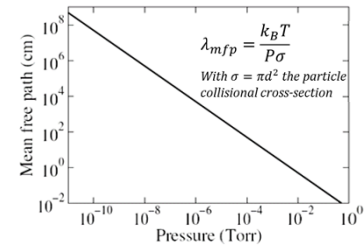
EPFL

Molecular Beam Epitaxy (MBE)



Ultra-high vacuum

✓ No interaction between atomic fluxes



✓ Use of *in situ* electron-beam monitoring (RHEED)

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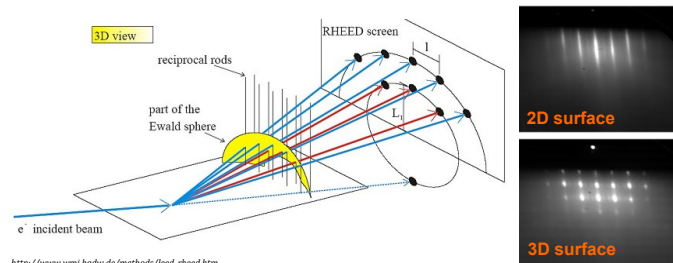
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Growth techniques

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Molecular Beam Epitaxy (MBE)

In situ Reflection High-Energy Electron Diffraction



➤ Surface roughness

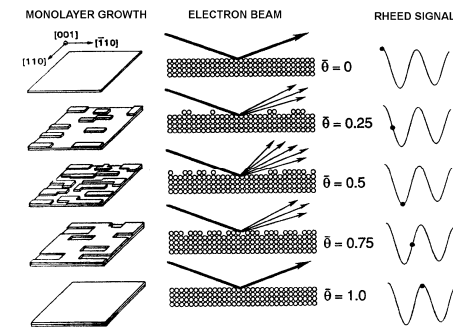
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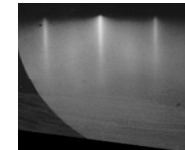
Growth techniques

EPFL

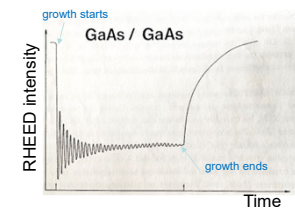
MBE growth: *in situ* monitoring with RHEED



J.H. Neave, B.A. Joyce, P.J. Dobson, N. Norton. Appl. Phys. A, 31 (1983)



Usually, new 2D-islands tend to appear on large growing 2D-islands
→ **damped oscillations**



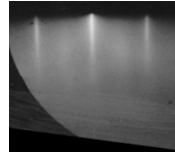
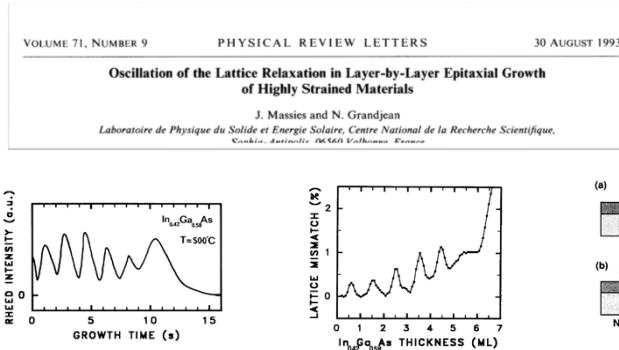
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Growth techniques

EPFL

MBE growth: *in situ* monitoring with RHEED



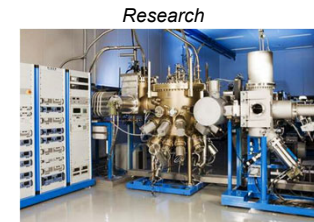
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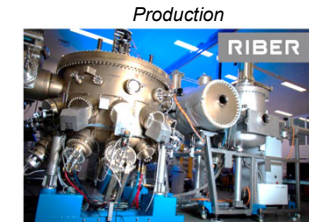
Growth techniques

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Molecular Beam Epitaxy (MBE)



- Up to 4" wafers
- II-VI, III-V (As, P, Sb, N), Oxides, SiGe, etc...



- Up to 5×8 " or 8×6 " wafers
- Mainly for GaAs-based HEMTs & HBTs
- Opportunities for VCSELs

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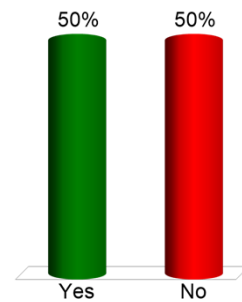
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Questions

EPFL

The critical thickness for plastic relaxation depends on the growth conditions

- A. Yes
B. No



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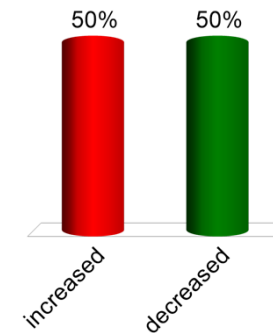
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Questions

EPFL

To promote the formation of SK-dots the surface energy should be

- A. increased
B. decreased



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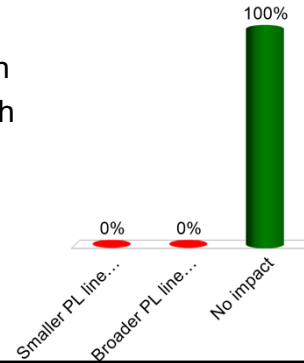
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Questions

EPFL

A quantum well with diffused interfaces, with respect to perfectly sharp ones, exhibits a

- A. Smaller PL linewidth
- B. Broader PL linewidth
- C. No impact



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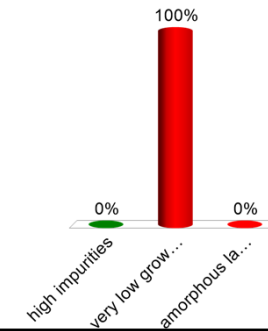
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Questions

EPFL

MOVPE is usually not well suited for low growth temperature process because of

- A. high impurities
- B. very low growth rate
- C. amorphous layer



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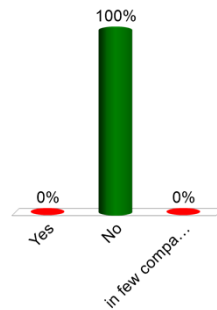
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Questions

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MBE is used for the production for blue LEDs

- A. Yes
- B. No
- C. in few companies



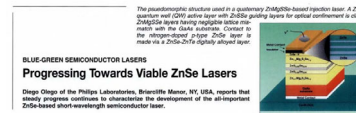
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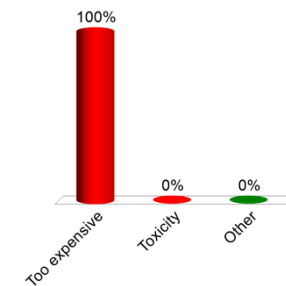
Questions

EPFL

II-VIs ((Zn,Cd)(S,Se)) have been investigated for blue LEDs and blue lasers but eventually abandoned. Why?



- A. Too expensive
- B. Toxicity
- C. Other



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